## **Supporting Information**

## Facile synthesis of flower-like nickel microspheres with

## enhanced microwave absorption properties

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Fig. S1 XRD pattern of precursor  $\alpha$ -Ni(OH)<sub>2</sub>



Fig. S2. SEM (a) and TEM (b) image of FNMs.



Fig. S3. SEM images of HNPs (a) and CNPs (b), and TEM images of HNPs (c) and CNPs (d).



Fig. S4. C<sub>0</sub> values of FNMs, CNPs and HNPs.



Fig. S5. Reflection loss curves of FNMs with the absorber thickness of 1.12 mm and 1.36 mm.



Fig. S6. SEM images of FNMs-400 (a), FNMs-450 (b), FNMs-500 (c), and FNMs-550 (d).



Fig. S7. Real parts (a) and imaginary parts (b) of relative complex permittivity, and real parts (c) and imaginary parts (d) of relative complex permeability for FNMs-400, FNMs-450, FNMs-550, and FNMs-550.



Fig. S8. Reflection loss characteristics of FNMs-400 (a), FNMs-450 (b), FNMs-500 (c), and FNMs-550 (d) with variable absorber thicknesses in the frequency range of 2.0-18.0 GHz.